

## ABSTRACT OF THE DISCLOSURE

While interior of a vacuum chamber is maintained to a specified pressure by introducing a specified gas into the vacuum chamber having a plasma trap provided therein and, simultaneously therewith, performing evacuation by a pump as an evacuating device, a high-frequency power of 100 MHz is supplied to a counter electrode by counter-electrode use high-frequency power supply. Thus, uniform plasma is generated within the vacuum chamber, where plasma processing such as etching, deposition, and surface reforming can be carried out uniformly with a substrate placed on a substrate electrode.

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